

# Plasma Etching

## *An Introduction*

Edited by

**Dennis M. Manos**

*Plasma Physics Laboratory  
Princeton University  
Princeton, New Jersey*

**Daniel L. Flamm**

*AT & T Bell Laboratories  
Murray Hill, New Jersey*



Academic Press  
San Diego New York Boston  
London Sydney Tokyo Toronto

INTEL 1113

This book is printed on acid-free paper. (∞)

Copyright © 1989 by Academic Press

All rights reserved.

No part of this publication may be reproduced or transmitted in any form or by any means, electronic or mechanical, including photocopy, recording, or any information storage and retrieval system, without permission in writing from the publisher.

**ACADEMIC PRESS**

*A Division of Harcourt Brace & Company*

525 B Street, Suite 1900

San Diego, California 92101-4495

*United Kingdom Edition published by*

**ACADEMIC PRESS INC. (LONDON) LTD.**

24-28 Oval Road, London NW1 7DX

**Library of Congress Cataloging-in-Publication Data**

**Plasma etching.**

(Plasma: materials interactions)

Bibliography: p.

Includes index.

1. Plasma etching. I. Manos, Dennis M. II. Flamm, Daniel L. III. Series: Plasma.

TA2020.P5 1988 621.044 87-37419

ISBN 0-12-469370-9

Alkaline paper

PRINTED IN THE UNITED STATES OF AMERICA

97 EB 9 8 7 6

# 3 An Introduction to Plasma Physics for Materials Processing

Samuel A. Cohen  
*Plasma Physics Laboratory  
Princeton University  
Princeton, New Jersey*

I. Introduction .....	186
II. The Plasma State .....	187
III. Single-Particle Motion .....	193
A. $E = \text{constant}, B = 0$ .....	194
B. $E = 0, B = \text{constant}$ .....	195
C. $E$ -perpendicular to $B$ .....	197
D. Non-Uniform Fields and Other Forces .....	198
E. Time-Varying Fields .....	201
F. Adiabatic Invariants .....	202
G. Summary of Particle Drifts .....	204
IV. Plasma Parameters .....	205
A. Temperature, Density, and Pressure .....	205
B. Debye Length and Plasma Frequency .....	207
C. Skin Depth and Dielectric Constant .....	213
D. Collisions .....	217
E. Summary of Plasma Parameters in Practical Units .....	229
F. Instabilities .....	229
G. Plasma Waves .....	238
V. Discharge Initiation .....	241
A. DC Glow .....	241
B. Microwave Breakdown .....	245
VI. An Application—The Planar Magnetron .....	248
Acknowledgements .....	258
References .....	258

## I. Introduction

The processing of materials by plasmas requires detailed knowledge in several scientific and technological areas. This is particularly true in the field of semiconductor fabrication where the continuing development of denser arrays with finer features has demanded the combination of various techniques into a highly specialized art. Perhaps the basic foundation for this art is plasma physics, though chemistry, electrical engineering, and vacuum technology have defensible claims. Each must be understood and well-practiced for the material processing to succeed.

In this chapter we will present the fundamental concepts in plasma physics which underlie the operation of plasma processing equipment. This will include discussions of the types of particles present in processing plasmas, their energies and fluxes, and an elucidation of the characteristic lengths, time scales, excitable modes (both stable and unstable), and atomic and surface processes important in the initiation and maintenance of plasma discharges. To discuss these topics in a practical way, we include information from a wide range of plasma configurations used in plasma processing, presenting material on dc- and rf-driven discharges with and without externally applied magnetic fields.

The understanding of plasmas that are unmagnetized, isothermal, isobaric, and isotropic is already rather difficult. The configurations used in all processing devices do not have even this simplicity, in large part due to the boundary between the plasma and the solid surfaces. It is at the boundary that our ultimate interests lie. However, the reader should find that the simplified situations described here will form a good understanding of the often counter-intuitive behavior of plasmas and will encourage improvements in existing equipment or processes.

Plasmas are usually created in metal vacuum vessels, commonly used to attain the low pressures essential for particular plasma properties. Plasmas have a propensity to fill every crevice in these vacuum vessels. (The word "plasma" originates from a Greek root meaning deformable.) And though efforts are made to constrain the plasma to particular sections of the vessel, these are not completely successful. Device operation is considerably affected. To emphasize this, we shall use the label "containment" vessels to fully appreciate that some plasma reaches everywhere in them.

We assume familiarity with college physics (especially Maxwell's equations) and introductory calculus. Most equations will be presented both in cgs and practical units to aid their easy application. Section II presents most of the basic ideas and definitions concerning plasmas. These are developed in the later sections. Section III concerns single-particle motion;

Section IV gives details of plasma parameters; Section V is devoted to plasma formation; and Section VI applies the previous four sections to the magnetron device.

## II. The Plasma State

Plasmas are a state of matter that consists of a large group of electrons and ions with nearly equal numbers of opposite charges, each particle moving at a high rate of speed relative to the others. It is the precise electric field of the individual charged particles that gives the plasma its unique properties. The electric field of each particle influences the motion of distant particles, whether they have like or opposite charge. This action-at-a-distance causes a wide variety of waves and instabilities to be possible in a plasma. And because each particle is influenced by the electric and magnetic fields of many particles, the term used to describe the kinematics is *collective motion*.

The electric field of a single isolated electron is proportional to  $r^{-2}$ . The volume of a spherical shell a distance  $r$  from that electron increases proportional to  $r^2$ . Thus, the product of the electric field times the volume, a measure of the effectiveness of the field at a distance, is constant (Fig. 1a). It is the same near the electron as it is far away, showing how the action-at-a-distance arises.

What differentiates a plasma from a group of neutral atoms that also has equal and large numbers of electrons and ions? It is the distance at which the electric field is felt strongly. Neutral atoms (and molecules) have an electric field no stronger than a dipole. This falls-off proportional to the distance cubed or faster. Hence at large distances, it is weak compared to the Coulomb electric field of the bare electrons found in a plasma. Because of the very short range of their electric and magnetic fields, molecules interact with each other only by "hard" collisions, meaning close encounters, typically at separations of about 1 Å. Free electrons and ions in a plasma interact over much greater distances, typically 1000 Å or more, as well as less, of course!

Numerous distant interactions will change a charged particle's trajectory more than the infrequent hard collisions (Fig. 1b). For this reason close encounters may be unimportant to the charged particles in a plasma. (This is related to another reason why a group of neutral atoms does not behave like a plasma. The quantal nature of the electronic energy levels in an atom precludes the small changes in energy required by distant encounters so important to plasma behavior.) Hence plasmas are frequently termed *colli-*

# Explore Litigation Insights

Docket Alarm provides insights to develop a more informed litigation strategy and the peace of mind of knowing you're on top of things.

## Real-Time Litigation Alerts



Keep your litigation team up-to-date with **real-time alerts** and advanced team management tools built for the enterprise, all while greatly reducing PACER spend.

Our comprehensive service means we can handle Federal, State, and Administrative courts across the country.

## Advanced Docket Research



With over 230 million records, Docket Alarm's cloud-native docket research platform finds what other services can't. Coverage includes Federal, State, plus PTAB, TTAB, ITC and NLRB decisions, all in one place.

Identify arguments that have been successful in the past with full text, pinpoint searching. Link to case law cited within any court document via Fastcase.

## Analytics At Your Fingertips



Learn what happened the last time a particular judge, opposing counsel or company faced cases similar to yours.

Advanced out-of-the-box PTAB and TTAB analytics are always at your fingertips.

## API

Docket Alarm offers a powerful API (application programming interface) to developers that want to integrate case filings into their apps.

## LAW FIRMS

Build custom dashboards for your attorneys and clients with live data direct from the court.

Automate many repetitive legal tasks like conflict checks, document management, and marketing.

## FINANCIAL INSTITUTIONS

Litigation and bankruptcy checks for companies and debtors.

## E-DISCOVERY AND LEGAL VENDORS

Sync your system to PACER to automate legal marketing.